

Positive-working photosensitive resin composition,
method for producing pattern-formed resin film,
semiconductor device, display device, and method
for producing the semiconductor device and the
display device

ABSTRACT

The invention provides a positive-working photosensitive resin composition comprising an alkali soluble resin (A), a diazoquinone compound (B) and a compound (C) which contains a $-CH_2OH$ group but not a phenolic hydroxyl group, a method for producing a pattern-formed resin film using the composition, a semiconductor device and a display device using the composition, and a method for producing the semiconductor device and the display device. Also, the present invention provides a positive-working photosensitive resin composition comprising an alkali soluble resin (A), a diazoquinone compound (B) and a mixture solvent of two or more kinds (D), wherein the mixture solvent (D) contains γ -butyrolactone and propylene glycol monoalkyl ether and the total amount of γ -butyrolactone and propylene glycol monoalkyl ether is about 70 wt% or more of the total amount of solvent, a method for producing a pattern-formed resin film using the composition, a semiconductor device and a display device using the composition, and a method for producing the semiconductor device and the display device.

FIG 1